

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	(silicon adj carbide adj substrate and non adj metallic adj mask adj layer and applying and layer and material and patterning and mask adj layer and expose and underlying adj areas and etching and plasma and first adj rate and lower).clm.	US-PGPUB	OR	ON	2005/12/23 16:30